

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 293482US0PCT		SERIAL NO. 10/588,080	
LIST OF REFERENCES CITED BY APPLICANT		APPLICANT					
		Naoyoshi HATAKEYAMA, et al.		FILING DATE January 10, 2007		GROUP <del>1752</del>	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
/VV/	AO	WO 03/104182 A1	12/18/2003	WIPO			
/VV/	AP	EP 0 999 474 A1	5/10/2000	Europe			
/VV/	AQ	EP 1 577 285 A1	9/21/2005	Europe			
/VV/	AR	EP 1 803 708 A1	7/4/2007	Europe			
	AS						
	AT						
	AU						
	AV						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
/VV/	AW	K. E. GONSALVES, et al., "High performance resist for EUV lithography", DATABASE CA [ONLINE], CHEMICAL ABSTRACTS SERVICE, XP-002461455, accession no. 2004: 1001937, Microelectronic engineering, 2005, 1 Page					
	AX						
	AY						
	AZ					<input type="checkbox"/> Additional References sheet(s) attached	
Examiner		/Yevgeny Valenrod/				Date Considered 03/23/2009	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							